



Substitute Form PTO-1449 (Modified)		U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 17979-034US1	Application No. 10/562,257
<b>Information Disclosure Statement by Applicant</b> (Use several sheets if necessary)  (37 CFR § 1.98(b))		Applicant Shafer et al.		
		Filing Date December 4, 2006	Group Art Unit 2621 2873	

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Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
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							Yes No
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	ATT	WO 2001/50171	07/12/2001	WIPO			English abstract
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	ASSS	Dammel et al., "193 nm Immersion Lithography – Taking the Plunge", Journal of Photopolymer Science and Technology, vol. 17 no. 4, pp 587-607 (2004).
	ATTT	Kawata et al., "Fabrication of 0.2mm Fine Patterns Using Optical Projection Lithography With an Oil Immersion Lens", Japanese Journal of Applied Physics, Japan Society of Applied Physics, Tokyo, Japan, vol. 31 no. 12B, Part 1, December 1, 1992, pp 4174-4177.
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<b>Other Documents (include Author, Title, Date, and Place of Publication)</b>		
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↓	AYYY	Smith, Bruce, "Water-based 193nm Immersion Lithography", Online!, <a href="http://www.sematech.org/resources/litho/meetings/immersion/20040128/presentations/06%20rit20\$microstepper%20effortsSmith.pdf">http://www.sematech.org/resources/litho/meetings/immersion/20040128/presentations/06%20rit20\$microstepper%20effortsSmith.pdf</a> , (January 28, 2004).

Examiner Signature	/William Choi/	Date Considered	11/12/2007
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